## Notice of References Cited Application/Control No. 09/901,837 Examiner Caridad M. Everhart Applicant(s)/Patent Under Reexamination BATRA ET AL. Page 1 of 1

## **U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	Α	US-	-		
	В	US-			
	С	US-			
	D	US-			
	Е	US-			
	F	US-			
	G	US-			
	Н	US-			
	1	US-			,
	J	US-			
	К	US-			
	٦	US-			
	М	US-			

## FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	0					
	Р				·	
	Q					
	R					
	s					
	Т					

## NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)				
	U	CC. Lee, et al. "roles of Ti-intermetallic compound layers on the electromigration resistance of Al-Cu interconnecting stripes" J. Appl. Phys. vol. 71, No. 12,(15 June 1992), pp. 5877-5887).				
	V					
	w					
	x					

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.